LITHOSCALE maskless exposure system from EV Group wins 2021 Best of West Award – December 8, 2021

SEMICONDUCTOR DIGEST DAILY

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Top Stories

LITHOSCALE maskless exposure system from EV Group wins 2021 Best of West Award

The LITHOSCALE maskless exposure system from EV Group (EVG) has won the 2021 Best of West award, SEMI and Semiconductor Digest announced today at SEMICON West 2021 Hybrid, December 7-9 at the Moscone Center in San Francisco. **More>>**

Reimagining simulation essential to create advanced chip designs. But how?

Past efforts to accelerate simulation with special-purpose hardware have repeatedly fallen behind the ever-improving performance of general-purpose computers, enabled by Moore's Law. But Moore's Law is ending, and the time is right to fundamentally rethink simulation algorithms, methodologies, and computational strategies. **More>>**

SEMICON West 2021 Hybrid Event | Dec 7-9

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Tech News

Increasing fab productivity with new chamber solutions

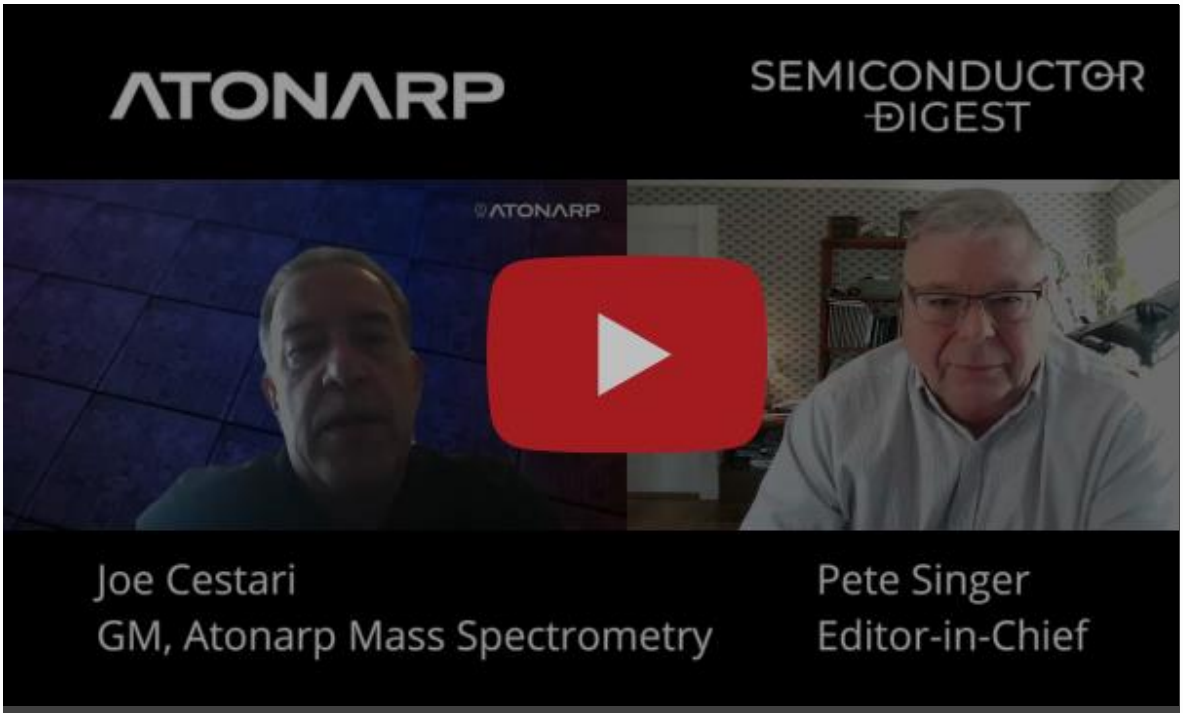
To speed throughput, equipment makers such as Applied Materials, Lam and TEL have implemented new tools that are smarter and denser. **More>>**

Microchip to provide silicon carbide MOSFETs and digital gate drivers for Mersen's SiC power stack reference design

Microchip Technology Inc. today announced the collaboration with Mersen on their 150 kilovolt-ampere (kVA) three-phase silicon carbide Power Stack Reference Design. **More>>**

Featured Video

Innovations in metrology can significantly boost yield, throughput, and efficiency for semiconductor fabs. **Atonarp Aston™** is helping to drive this innovation forward, as a robust compact mass spectrometer designed from the ground up to be the workhorse metrology tool for gas monitoring and control in semiconductor manufacturing. High quantitative accuracy and real-time performance are combined with production-ready robustness and dependability, helping to increase process chamber throughput and maximize yields of high-precision, multi-layer material deposition and etch processes in production environments. With a high level of flexibility and an integrated plasma ionization source, Aston is a single tool ready to support the broadest class of semiconductor metrology needs, including the increasingly precise in-situ process management required in today's industry.



Atonarp — Advanced Metrology to Increase Yield & Throughput

Business News

Semiconductor market has surpassed $150B in a single quarter as Samsung takes over top spot in revenue ranking

Semiconductor revenue rose 7.6% in Q3 2021 from Q2 2021 and climbed above $150 billion in

revenue during a single quarter for the first time since research group Omdia began tracking the market in 2002. **More>>**

Intel launches Integrated Photonics Research Center

Intel Labs recently opened the Intel Research Center for Integrated Photonics for Data Center Interconnects. **More>>**

Featured Product

Pfeiffer Vacuum ATH 2804 M/MT and ATH 3204 M/MT magnetically levitated turbopumps are designed for harsh semiconductor applications. They offer a gas throughput of over 5,000 sccm of nitrogen for non-heated applications and up to 1,500 sccm of argon at 65°C in corrosive applications. **Learn more.**

Webcasts and Technology Papers

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Analysis of Metallic Impurities in Si Wafers Using Fully Automated VPD-ICP-MS
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Managing the Emission Properties of MicroLEDs Through Photonic Bandgap Engineering
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